	Application No.	Applicant(s)	
Notice of Allowability	Application No.	Applicant(s)	
	09/903,764	OKU ET AL.	
	Examiner	Art Unit	
	Khiem D Nguyen	2823	
The MAILING DATE of this communication app. All claims being allowable, PROSECUTION ON THE MERITS I herewith (or previously mailed), a Notice of Allowance (PTOL-8 NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT of the Office or upon petition by the applicant. See 37 CFR 1.3	S (OR REMAINS) CLOSED 5) or other appropriate comn RIGHTS. This application is	in this application. If not included nunication will be mailed in due cou	ırse. THIS
1. This communication is responsive to <u>08/02/04</u> .			
2. ☑ The allowed claim(s) is/are <u>1,2,4,5,8,19 and 20</u> .			
 3. ☐ The drawings filed on 13 July 2001 are accepted by the 	Examiner		
4. Acknowledgment is made of a claim for foreign priority u		or (f)	
a) ☑ All b) ☐ Some* c) ☐ None of the:	macr 55 6.6.6. g 119(a)-(u)	or (1).	
 Certified copies of the priority documents have 	ve been received.		
Certified copies of the priority documents had	• •		
Copies of the certified copies of the priority of	ocuments have been receive	ed in this national stage application	from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
5. Acknowledgment is made of a claim for domestic priority			
(a) The translation of the foreign language provisional			
6. Acknowledgment is made of a claim for domestic priority	under 35 U.S.C. §§ 120 and	/or 121.	
Applicant has THREE MONTHS FROM THE "MAILING DATE" below. Failure to timely comply will result in ABANDONMENT of the complex o	of this application. THIS THIS THIS THIS THIS THIS THIS THIS	REE-MONTH PERIOD IS NOT EXT KAMINER'S AMENDMENT OF NOT	TENDABLE
	,		
8. CORRECTED DRAWINGS must be submitted.			
(a) ☐ including changes required by the Notice of Draftspo	erson's Patent Drawing Revi	ew (PTO-948) attached	
1) hereto or 2) to Paper No			
(b) ☐ including changes required by the proposed drawing			
(c) ☐ including changes required by the attached Examine	er's Amendment / Comment	or in the Office action of Paper No.	
Identifying indicia such as the application number (see 37 CFR each sheet.	1.84(c)) should be written on	the drawings in the front (not the bac	:k) of
9. DEPOSIT OF and/or INFORMATION about the department of attached Examiner's comment regarding REQUIREMENT FOR	osit of BIOLOGICAL MAT THE DEPOSIT OF BIOLOG	ERIAL must be submitted. Note ICAL MATERIAL.	the
Attachment(s)			
1 Notice of References Cited (PTO-892)	2☐ Notice	of Informal Patent Application (PTC	D-152)
3☐ Notice of Draftperson's Patent Drawing Review (PTO-948)) 4 Interview Summary (PTO-413), Paper No		
5 Information Disclosure Statements (PTO-1449), Paper No.	• • • • • • • • • • • • • • • • • • • •		
7 Examiner's Comment Regarding Requirement for Deposit of Biological Material	8⊠ Examir 9⊡ Other	er's Statement of Reasons for Allo	wance

EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

The application has been amended as follows:

In claim:

Cancel non-elected claims 9-18.

Allowable Subject Matter

Claims 1, 2, 4, 5, 8, 19 and 20 are allowed.

Reasons For Allowance

The following is a statement of reasons for the indication of allowable subject matter: The prior art taken alone or in combination neither discloses nor makes obvious the instant process of claims as a whole. Specifically, the prior art of record, Takeda et al. (U.S. Pub. 2003/0111730) disclose a film forming method for forming a siliconcontaining barrier insulating film on a substrate comprising the steps of: preparing a filmforming gas comprising, (1) at least one member selected from the group consisting of alkoxy compounds having Si-H bonds (page 3, paragraphs [0019] and [0044]) and (2) at least one oxygen-containing gas selected from the group consisting of O₂, N₂O, NO₂, CO, CO₂, and H₂O; contacting the substrate with the plasma to form the silicon-containing barrier insulating film (P-TMS) (FIG. 6(c): 206) on the substrate (FIG. 6(c): 100) (page 6, paragraphs [0059]-[0062] and FIGS. 1-17); and forming a porous insulating film (FIG.

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6(c): 207) by plasma enhanced CVD as an interlayer insulating film directly on the barrier insulating film (page 7, paragraph [0067]) but fails to teach or suggest the Applicant's steps of preparing a film-forming gas comprising, (1) at least one member selected from the group consisting of siloxane compounds having Si-H bonds and (2) at least one oxygen-containing gas selected from the group consisting of O₂, N₂O, NO₂, CO, CO₂, and H₂O and converting the film-forming gas into a plasma as recited in the independent claims.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Khiem D Nguyen whose telephone number is (571) 272-1865. The examiner can normally be reached on Monday-Friday (8:00 AM - 5:00 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Olik Chaudhuri can be reached on (571) 272-1855. The fax phone numbers for the organization where this application or proceeding is assigned are (703) 305-3432 for regular communications and (703) 305-3432 for After Final communications.

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Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-0956.

K.N. August 18, 2004

> W. DAVID COLEMAN PRIMARY EXAMINER